

Application No.: 10/076003

Case No.: 57181US002

Amendments to the Claims

20. (amended) An integrated circuit comprising:
a deposition substrate;
a patterned first electrode layer formed adjacent the deposition substrate;
a patterned organic semiconductor layer formed adjacent the first electrode layer; and
a second patterned electrode layer deposited adjacent the organic semiconductor layer,
wherein [each patterned layer is] the patterned first electrode layer, the patterned organic semiconductor layer, and the second patterned electrode layer are each defined by a repositionable aperture mask.

39. (new) The integrated circuit of claim 20 wherein at least one of said first electrode layer, said patterned organic semiconductor layer or said second patterned electrode layer is vapor deposited.

40. (new) The integrated circuit of claim 20 wherein each of said first electrode layer, said patterned organic semiconductor layer or said second patterned electrode layer are vapor deposited.